

ABSTRACTSUBSTRATE LOADING APPARATUS

5 The present invention provides apparatus for loading
a substrate (65) onto a processing surface (61) in a thin-
film processing chamber (60). The apparatus includes a
support (66) which cooperates with one or more
10 corresponding apertures (62) in the processing surface so
as to be movable between an extended position in which the
support can support a substrate (65) above the processing
surface (61), and a retracted position in which the support
is flush with or located below the processing surface (61).
The support has a number of limbs (64) which extend
15 radially outwardly from a central hub, at an angle relative
to the processing surface. The limbs contact the edges of
different sized substrates in use so as to support the
substrate in a support plane above the central hub and
substantially parallel to the processing surface.